

<b>FORM PTO-1449 U.S. Department of Commerce</b> Patent and Trademark Office  <b>LIST OF DOCUMENTS CITED BY APPLICANT</b>  (Use several sheets if necessary)				Attorney Docket Number 5576-137		Serial No. to be assigned	
				Applicants: Satoshi Watanabe			
				Filing Date concurrently herewith		Gross 1752	

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U. S. PATENT DOCUMENTS							
Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate	
yct	5,569,784	10/29/96	Watanabe et al.	564	430		
yct	5,580,695	12/03/96	Murata et al.	430	270.1		
yct	5,972,559	10/26/99	Watanabe et al.	430	270.1		
	6,150,068	11/21/00	Sato et al.	430	270.1		

FOREIGN PATENT DOCUMENTS							
Document Number	Date	Country	Class	Subclass	Translation Yes   No		
yct	5249683	09/28/93	Japan	G03F	007/075	X (abstract)	
yct	10048814 A	02/20/98	Japan	G03F	007/004	X (abstract)	
yct	10073912	03/17/98	Japan	G03F	001/00	X (abstract)	
yct	10133371	05/22/98	Japan	G03F	007/029	X (abstract)	
yct	10142777	05/29/98	Japan	G03F	007/004	X (abstract)	
yct	10319581 A	12/04/98	Japan	G03F	007/004	X (abstract)	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)		
yct	Hinsberg et al., "Fundamental Studies of Airborne Chemical Contamination of Chemically Amplified Resists," <i>Journal of Photopolymer Science and Technology</i> , 6(4): 535-546 (1993).	
yct	Houlihan et al., "A Study of Resist Outgassing as a Function of Differing Photadditives," <i>Proc. SPIE</i> , 3678: 264-274 (1999).	
yct	Uetani et al., "Positive ArF Resist with 2EAdMA/GBLMA Resin System," <i>Proc. SPIE</i> , 3678: 510-517 (1999).	

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DATE CONSIDERED

8/28/03

Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.